

Supporting information

Highly efficient and stable quantum dot light-emitting devices with low-temperature tin oxide electron transport layer

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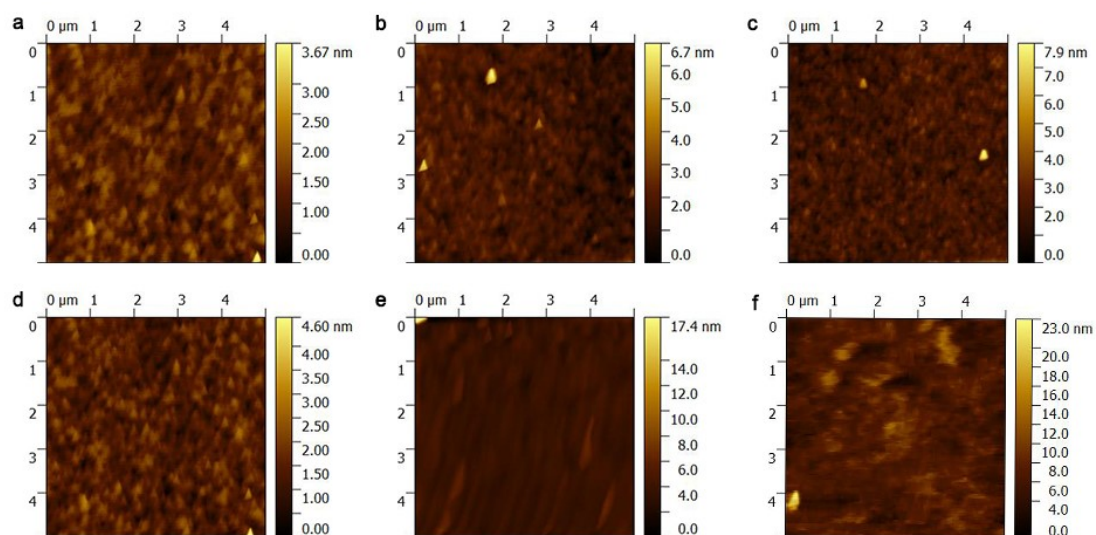


Figure S1 The surface morphology images of ITO/SnO₂ films under the annealing temperature of 120, 140, 160, 180, 200, 260 °C, respectively.

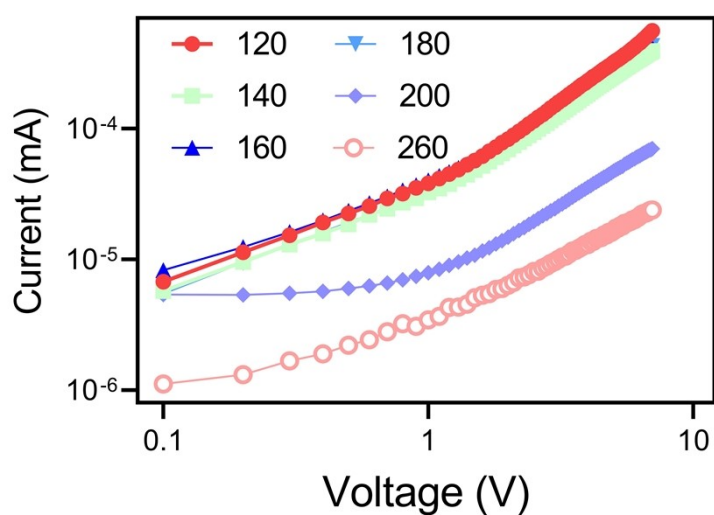


Figure S2 The lateral conductivity of ITO/SnO₂ film with the annealing temperature of 120, 140, 160, 180, 200, and 260 °C, respectively.

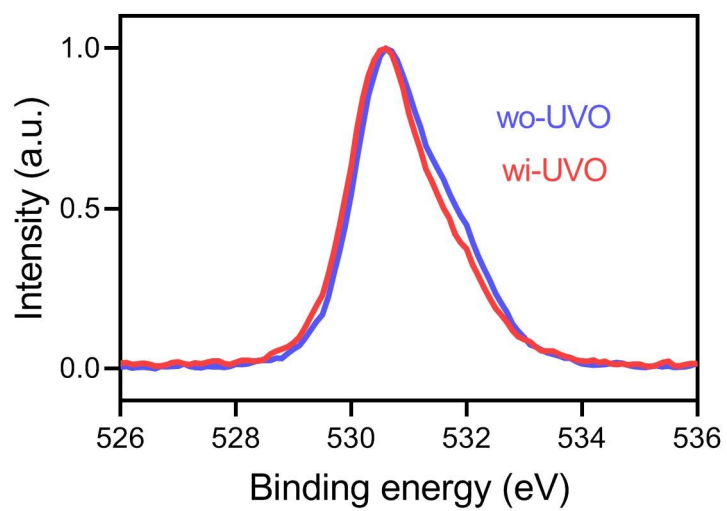


Figure S3 The combined figure of high-resolution O 1s spectra of wo-UVO and the wi-UVO films.